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| Form PTO-1449 | | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | | ATTY. DOCKET NO. MI22-2395 | | Priority SERIAL NO. 10/208,154 | |
| LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) | | | | APPLICANT Jerome M. Eldridge | | Priority FILING DATE July 29, 2002 | |
| | | | | Priority GROUP 2822 | | | |

| U.S. PATENT DOCUMENTS | | | | | | | |
|-----------------------|-----------------|-----------|----------|-------------------|----------|----------------------------|--|
| *Examiner Initial | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | |
| KED ↓ | AA | 5,350,738 | 9/27/94 | Hase et al | | | |
| | AB | 5,350,738 | 09/19/94 | Hase et al | | | |
| | AC | 5,272,341 | 12/1/93 | Micheli et al | | | |
| | AD | 5,142,437 | 08/1/992 | Kammerdiner et al | | | |
| | AE | 6,461,931 | 10/2002 | Eldridge | | | |
| | AF | 6,025,257 | 02/2000 | Jeon, Yoo Chan | | | |
| | AG | 5,789,268 | 08/1998 | Chivukula | | | |
| | AH | | | | | | |
| | AI | | | | | | |

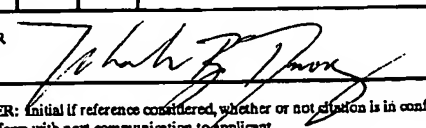
| FOREIGN PATENT DOCUMENTS | | | | | | | |
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| Document Number | Date | Country | Class | Subclass | Translation | | |
| | | | | | Yes | No | |
| AJ | | | | | | | |
| AK | | | | | | | |
| AL | | | | | | | |
| AM | | | | | | | |

| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | |
|---|----|--|
| KED ↓ | AN | John Baliga, "New Materials Enhance Memory Performance", Semiconductor International, November 1999, pgs. 1-8. |
| | AO | "Advances in Ultrathin Oxides and Oxynitrides I", Materials Research Society Symposium Proceedings Series, Vol. 567, April 5, 1999, 2 pages. |
| | AP | K.S. Tang, W.S. Lau, and G.S. Samudra, "Trends in Dram Dielectrics", IEEE Circuits & Devices, Vol. 13, No. 3, May 1997, pgs. 27-34 |
| | AQ | D.W. Hess, "Plasma-assisted oxidation, anodization, and nitridation of silicon", IBM Journal of Research & Development, Vol. 43, No. 1/2, Plasma processing, 22 pages. |
| | AR | O. Kubaschewski, E. LL. Evans, "Metallurgical Thermochemistry", Pergamon Press, 1958, pgs. 226-227 and 336-337 |
| | AS | Ting, Chen, Liu, "Structural evolution and Optical properties of TiO ₂ thin films prepared by thermal oxidation of sputtered Ti films", Journal of Applied Physics, Vol. 88, Number 9, 15 October 2000, pgs. 4628-4633. |
| | AT | O. Kubaschewski, B.E. Hopkins, "Oxidation of Metals and Alloys", Butterworths London, Second Edition, 1962, pgs. 36-37 and 70-73. |
| | AU | F.P. Fehlner, "Low-Temperature Oxidation", Monograph published by Electrochemical Society, Pennington, New Jersey, 1983, pgs. 31-35. |
| | AV | Richard A. Swalin, "Thermodynamics of Solids", Second Edition, Chapter 5, John Wiley & Sons, 1972, pgs. 112-115. |

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| EXAMINER <i>John B. Phony</i> | DATE CONSIDERED <i>8/22/2004</i> |
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*EXAMINER: initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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| Form PTO-1449 | | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | | ATTY. DOCKET NO. M22-1667 | SERIAL NO. Filed Herewith | | | |
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| LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) | | | | APPLICANT Jerome M. Eldridge | | | | |
| | | | | FILING DATE Filed Herewith | GROUP Unknown | | | |
| U.S. PATENT DOCUMENTS | | | | | | | | |
| *Examiner Initial | | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | |
| KBD | AA | 09/651,380 | | Eldridge (as filed and amended 3/28/02) | | | 8/29/00 | |
| | AB | | | | | | | |
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|  | | | | 8/22/2004 | | | | |
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